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Devices and preparation methods for niobium coupon samples used to investigate high-Q mechanism

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A surface treatment device has been established at the Wuxi Platform, enabling chemical polishing treatment on coupon samples. Currently, several samples treated with buffered chemical polishing (BCP) have been utilized in the investigation of nitrogen doping and medium-temperature baking mechanisms. This paper presents the development process of this device along with the experimental outcomes. In the future, we plan to enhance the device to facilitate electropolishing (EP) treatment on coupon samples.

Footnotes

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Primary author: ZONG, Yue (Shanghai Institute of Applied Physics)

Co-authors: WANG, Dong (Shanghai Advanced Research Institute); WU, Jiani (Shanghai Advanced Research Institute); CHEN, Jinfang (Shanghai Advanced Research Institute); XING, Shuai (Shanghai Advanced Research Institute); WANG, Zheng (Shanghai Institute of Applied Physics)

Presenter: ZONG, Yue (Shanghai Institute of Applied Physics)

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